Oxford Instruments Plasma Technology & Institute of Semiconductors (IOS) China



Seminar on

Nanoelectronics: Growth, deposition, etching

11-12th March 2011

Presented by:

Institute of Semiconductors Chinese Academy of Sciences (IOS) & Oxford Instruments Plasma Technology

Venue: Xi-Jiao hotel, Haidian District, Beijing

Agenda

11th March 2011

10.00 – 10.15	Welcome Coffee			
10.15-10.30	Introduction	Mark Vosloo / Jeffrey Seah, Oxford Instruments		
10.30 – 11.00	Welcome by IOS Semiconductor micro-and nano- technology application in IOS	Prof. YANG Fuhua, Institute of Semiconductors, CAS		
11.00 – 11.30	Si Etching review	Robert Gunn, Oxford Instruments		
11.30 – 12.00	III/ V Etching Overview	Dr Ligang Deng, Oxford Instruments		
12.00 – 13.00	Lunch			
13.00 – 14.00	Fabrication of Dielectric Coatings using Optofab3000 Ion Beam Sputtering Deposition System	Dr. WANG Xiaodong, Institute of Semiconductors, CAS		
14.00 – 14.30	The application of ICP dry etching in the fabrication of novel semiconductor optoelectronic devices	Dr. HAN Yanjun, Tsinghua University		
14:30 - 15:00	ALD overview	Dr Qi Fang, Oxford Instruments		
15.00 – 15.30	Nanoscale etching	Deirdre Olynick, Molecular Foundry, LBNL, CA USA		
15.30 – 16.15	Round table question and answer discussion on III-V etch, Si, SiO2 etch, PECVD dep, ALD dep	Chair: Robert Gunn, Oxford Instruments, with Dr Ligang Deng, Dr Qi Fang and jada Wang (Oxford Instruments) & Guest speakers		



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Agenda

12th March 2011

9.00 – 9.30	ICP CVD/PECVD	Bob Gunn, Oxford Instruments	
9.30 – 10.00	III-V Compound Semiconductor Dry Etching using Plasmalab System100	Dr. FAN Zhongchao, Institute of Semiconductors, CAS	
10.00-10.30	Nanofabrication by ICP-RIE etching ICP-RIE	Dr. XIA Xiaoxiang, Institute of Physics	
10.30-11.00	Talk to be confirmed	Guest speaker from Europe	
11:00 – 12.30	IOS Cleanroom tour	Organised by the hosts, IOS	
12.30 – 13.30	Closing remarks/Questions/Lunch		

To make a booking or for further information on this seminar please contact:

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NOTE: There is no charge for this seminar, but advance booking is essential

Please note: Details in this document are correct at the time of publishing and will be subject to change

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